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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/713,172 11/14/2003		Aaron Partridge	11403/84	9823
26646 KENYON & K	7590 02/26/200 ENYON LLP	EXAMINER		
ONE BROADV	VAY	SMITH, FRANCIS P		
NEW YORK, N	N1 10004		ART UNIT	PAPER NUMBER
		1792		
			MAIL DATE	DELIVERY MODE
			02/26/2009	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/713,172	PARTRIDGE ET AL.	
Examiner	Art Unit	
Francis P. Smith	1792	

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	Francis P. Smith	1792			
The MAILING DATE of this communication appe	ears on the cover sheet with the o	correspondence add	ress		
THE REPLY FILED <u>17 February 2009</u> FAILS TO PLACE THIS	APPLICATION IN CONDITION FO	R ALLOWANCE.			
1. The reply was filed after a final rejection, but prior to or on application, applicant must timely file one of the following application in condition for allowance; (2) a Notice of Appelor Continued Examination (RCE) in compliance with 37 Coperiods:	the same day as filing a Notice of replies: (1) an amendment, affidavieal (with appeal fee) in compliance	Appeal. To avoid abar t, or other evidence, w with 37 CFR 41.31; or	which places the (3) a Request		
a) The period for reply expires <u>3</u> months from the mailing date	of the final rejection.				
b) The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection.					
Examiner Note: If box 1 is checked, check either box (a) or (MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f).				
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of extunder 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b). NOTICE OF APPEAL	tension and the corresponding amount shortened statutory period for reply origi than three months after the mailing dat	of the fee. The appropria nally set in the final Offic	ate extension fee se action; or (2) as		
2. The Notice of Appeal was filed on A brief in comp	liance with 37 CFR 41.37 must be	filed within two months	s of the date of		
filing the Notice of Appeal (37 CFR 41.37(a)), or any exter Notice of Appeal has been filed, any reply must be filed w	nsion thereof (37 CFR 41.37(e)), to	avoid dismissal of the	appeal. Since a		
<u>AMENDMENTS</u>					
3. The proposed amendment(s) filed after a final rejection, by	out prior to the date of filing a brief,	will <u>not</u> be entered be	cause		
(a) ☐ They raise new issues that would require further collished. (b) ☐ They raise the issue of new matter (see NOTE belo		i ⊨ below);			
(c) They are not deemed to place the application in bet	•	ducina or simplifyina tl	ne issues for		
appeal; and/or	ter form for appear by materially rec	adding or aimpinying ti	10 100000 101		
(d) They present additional claims without canceling a	corresponding number of finally reje	ected claims.			
NOTE: See Continuation Sheet. (See 37 CFR 1.1	16 and 41.33(a)).				
4. The amendments are not in compliance with 37 CFR 1.12	21. See attached Notice of Non-Co	mpliant Amendment (PTOL-324).		
5. Applicant's reply has overcome the following rejection(s):	:				
 Newly proposed or amended claim(s) would be all non-allowable claim(s). 	·	•	_		
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is proving the status of the claim(s) is (or will be) as follows: Claim(s) allowed:		I be entered and an e	xplanation of		
Claim(s) objected to:					
Claim(s) rejected: <u>1-30 and 41-56</u> .					
Claim(s) withdrawn from consideration: AFFIDAVIT OR OTHER EVIDENCE					
8. ☐ The affidavit or other evidence filed after a final action, bu	t before or on the date of filing a No	otice of Appeal will not	be entered		
because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e).					
 The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to o showing a good and sufficient reasons why it is necessary 	vercome <u>all</u> rejections under appea	al and/or appellant fail:	s to provide a		
10. ☐ The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER	n of the status of the claims after e	ntry is below or attach	ed.		
 The request for reconsideration has been considered bu <u>See Continuation Sheet.</u> 	t does NOT place the application in	condition for allowan	ce because:		
12. Note the attached Information <i>Disclosure Statement</i> (s). (13. Other:	(PTO/SB/08) Paper No(s)				
/Michael Kornakov/ Supervisory Patent Examiner, Art Unit 1792	/Francis Smith/, Examiner				

Continuation of 3. NOTE: Amendment to claims 1 and 41, if entered, changes the scope of the dependent claims, which would require at least additional consideration and possibly a new search.

Continuation of 11. does NOT place the application in condition for allowance because: Applicants argue the prior art reference to Yu does not "disclose or suggest forming a silicon dioxide layer which includes heating a substrate to anneal a sub-layer of the silicon oxide layer, where the temperature to which the substrate is heated for the annealing is approximate to a highest processing temperature applied subsequent to the forming of the silicon oxide layer". The examiner respectfully disagrees. In examples 1-5, Yu clearly teaches forming a silicon oxide layer at a first temperature (e.g. 920 C). Subsequently, Yu's examples 6-8 teach applying a post anneal step "having formed thereupon the gap filling silicon oxide layer" (col. 10, lines 56-66). Furthermore, it has been held that the selection of any order of performing process steps is prima facie obvious in the absence of new or unexpected results. It is also noted that the secondary reference to Ito at least teaches forming a silicon oxide layer (e.g. at a first temperature), heating the substrate to a second temperature wherein the second temperature is approximate to the highest processing temperature subsequently applied to the substrate following the formation of the silicon oxide layer, and whereby the film is formed by an iterative process (see Ito; col. 3, line 64-col. 4, line 4, 49-65). Applicants also argue that the Yu/lto combination does not disclose nor suggest forming a silicon oxide layer with a compressive stress. However, it is noted that Yu/Ito teach substantially the same process steps as those recited in claim 11. As per Applicants' argument that Yu/Ito does not disclose or suggest "forming a silicon oxide layer with a compressive stress," it is axiomatic that one who performs the steps of a process must necessarily produce all of its advantages and the mere recitation of a newly discovered property that is inherently possessed by the steps in the prior art does not cause a claim drawn to those steps to distinguish over the prior art. Furthermore, independent claims 1 and 41 are currently amended, which changes the scope of at least the dependent claims; and there, additional considerations are deemed necessary.